



Joint Symposium on Direct Write, Optical, Ion and Electron Beam Lithography Thursday, 03.12.2020

This symposium features technical experts and customers from Nanoscribe, micro resist technology, GenISys and Raith who will describe the spectrum of latest, state-of-the-art direct-write capabilities.

09:30 – 09:40

Welcome and Introduction

09:40 – 10:10

Highlights in photopolymer development for advanced micro & nanopatterning technologies

Anja Voigt, micro resist technology GmbH

10:10 – 10:40

Nanofabrication for quantum computing

Michael Kahl, Raith GmbH

10:40 – 11:10

Towards photonic neuromorphic computing

Prof. Dr. Wolfram Pernice, WWU Münster

11:10 – 11:40

3D Laser Lithography of Stimuli-Responsive Hydrogels

Marc Hippler, KIT Karlsruhe

11:40 – 12:10

Material Innovations for 3D Microprinting

Jochen Zimmer, Nanoscribe GmbH

12:10 – 13:00

Lunch Break

13:00 – 13:30

Electron Beam Lithography Software Enabling Quantum Devices

Nezih Unal, GenISys GmbH

13:30 – 14:00

From electrons to photons - applications for direct write lithography

Helmut Schift, Paul Scherrer Institut, Villigen PSI, Switzerland

14:00 – 16:00

Process Clinic (open discussion about process related challenges)

